



AF ZMW

PATENT
Customer No. 22,852
Attorney Docket No. 4329.2543-01

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:)
Masamitsu Itoh et al.) Group Art Unit: 1752
Application No.: 10/665,616) Examiner: Amanda C. Walke
Filed: September 22, 2003)
For: PATTERN FORMATION) Confirmation No.: 6561
MATERIAL, PATTERN)
FORMATION METHOD, AND)
EXPOSURE MASK)
FABRICATION METHOD)

Mail Stop AF
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

REQUEST FOR RECONSIDERATION

In reply to the Final Office Action mailed December 21, 2004, the period for response extending through March 21, 2005, Applicants submit the following remarks.

Attachments to this amendment include a partial translation of Sato et al. (JP 09-262721).